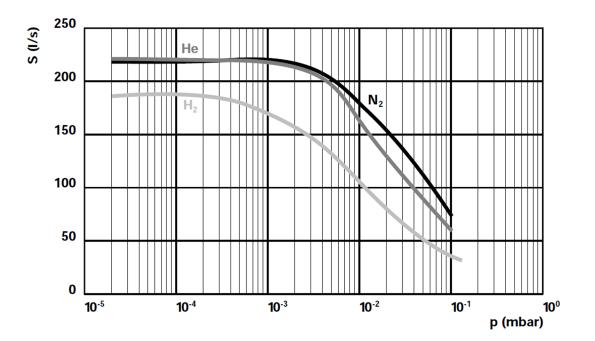


Pfeiffer TMH-262, TMU-262 Technical Specifications

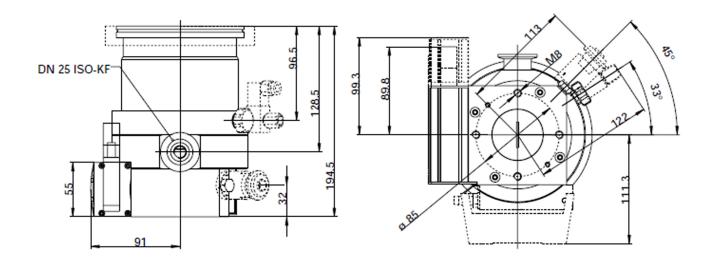
Pumping speed: for N ₂	210 l/s
Pumping speed: for He	220 I/s
Pumping speed: for H ₂	190 l/s
Compression ratio for N ₂	1.10 ⁹
Compression ratio for He	3·10 ⁵
Compression ratio for H ₂	1.3·10 ⁴
Gas throughput for N ₂	7 mbar I/s
Gas throughput for He	6 mbar I/s
Gas throughput for H ₂	3.5 mbar I/s
Ultimate pressure with rotary vane pump	TMH < 1.10 ⁻⁷ mbar,
	TMU < 5·10 ⁻¹⁰ mbar
Ultimate pressure with diaphragm pump	TMH < 1.10^{-7} mbar
entitude presedure that diapriragin pump	inviti si to modi,
o annaco processi o mar arapin agin pamp	TMU < 1.10^{-8} mbar
Recommended backing pump	
	TMU < 1.10 ⁻⁸ mbar
	TMU < 1.10 ⁻⁸ mbar MVP 015-2, MVP 035-2,
Recommended backing pump	TMU < 1·10 ⁻⁸ mbar MVP 015-2, MVP 035-2, DUO 5
Recommended backing pump Rotational speed ±2%	TMU < 1.10 ⁻⁸ mbar MVP 015-2, MVP 035-2, DUO 5 60000 1/min
Recommended backing pump Rotational speed ±2% Rotational speed: variable %	TMU < 1.10 ⁻⁸ mbar MVP 015-2, MVP 035-2, DUO 5 60000 1/min 20-100
Recommended backing pump Rotational speed ±2% Rotational speed: variable % Run-up time	TMU < 1.10 ⁻⁸ mbar MVP 015-2, MVP 035-2, DUO 5 60000 1/min 20-100 3.5 min
Recommended backing pump Rotational speed ±2% Rotational speed: variable % Run-up time Cooling method	TMU < 1.10 ⁻⁸ mbar MVP 015-2, MVP 035-2, DUO 5 60000 1/min 20-100 3.5 min water, air
Recommended backing pump Rotational speed ±2% Rotational speed: variable % Run-up time Cooling method Cooling water consumption	TMU < 1.10 ⁻⁸ mbar MVP 015-2, MVP 035-2, DUO 5 60000 1/min 20-100 3.5 min water, air 100 I/h



Pfeiffer TMH-262, TMU-262 Pumping Curves



Dimensions



Provac Sales, Inc. 3131 Soquel Drive, Soquel CA 95073



Pfeiffer TMH-262, TMU-262

Features & Benefits

- pump and drive form single unit
- simple and economical system solution
- modular design for maximum flexibility
- all components connects on the plug & play principle
- minimal space requirements for the entire system
- integrated serial interface provides additional versatility

Applications

- semiconductor processes
 thin film coatings
 mass spectrometry
- process gas monitors
 research and development
 UHV technology
- $\cdot \, \mathsf{HV} \, \mathsf{technology} \cdot \mathsf{vacuum} \, \mathsf{processing} \cdot \mathsf{accelerators} \cdot \mathsf{fusion}$

Recommended backing pumps

- Diaphgragm pumps: MVP 015-2 MVP 035-2 MVP 055-3
- Vane pumps; DUO 5